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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Ko et al.

Application No: 09/894,230

Filed: June 27, 2001

For: APPARATUS AND METHOD FOR ARGON
PLASMA INDUCED ULTRAVIOLET LIGHT
CURING STEP FOR INCREASING SILICON-
CONTAINING PHOTORESIST SELECTIVITY

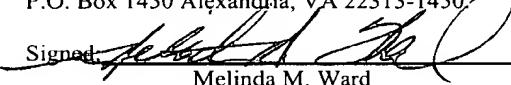


) Docket No: LAM2P257
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Group Art Unit: 1756
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Examiner: J. Ruggles
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June 2, 2003
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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as
First Class Mail to: Commissioner for Patents
P.O. Box 1450 Alexandria, VA 22313-1450.

Signed: 
Melinda M. Ward

AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

This Communication is in response to the Office Action dated March 3, 2003.
Please amend the application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the claims are reflected in the listing of claims which begins on page 4 of
this paper.

Amendments to the drawings begin on page 7 and include attached replacement sheets.

Remarks/Arguments begin on page 8 of this paper.